

FORM PTO-1449
(REV. 7-80)U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.
RD-28,292SERIAL NO.
09/836,657INFORMATION DISCLOSURE STATEMENT BY APPLICANT
LIST OF ITEMSApplicant
Argemiro Soares da Silva SobrinhoFiling Date
4/17/01Group
2871

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	A1					
	A2					
	A3					
	A4					
	A5					

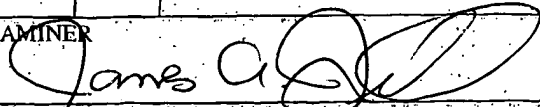
FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
	B1					
	B2					

OTHER INFORMATION (Including Author, Title, Date, Pertinent Pages, etc.)

0	C1	AS da Silva Sobrinho et al, "A Study of Defects in Ultra-Thin Transparent Coatings on Polymers", Applied Physics A, Materials Science & Processing, 68, pp. 103-105, 1999.				
0	C2	AS da Silva Sobrinho et al, "A Study of Defects in Ultra-Thin Transparent Coatings on Polymers", Surface & Coatings Technology, 116-119, pp. 1204-1210, 1999.				
0	C3	AS da Silva Sobrinho et al, "Defect-Permeation Correlation for Ultrathin Transparent Barrier Coatings on Polymers", J. Vac. Sci. Technol. A 18(1), American Vacuum Society, pp 149-157, 2000.				
0	C4	AS da Silva Sobrinho et al, "Plasma-Deposited Silicon Oxide and Silicon Nitride Films on Poly(ethylene terephthalate): A Multitechnique Study of the Interphase Regions", J. Vac. Sci. Technol. A 16(4), American Vacuum Society, pp 2021-2030, 1998.				
0	C5	AS da Silva Sobrinho et al, "Transparent Barrier Coatings on Polyethylene Terephthalate By Single- and Dual-Frequency Plasma-Enhanced Chemical Vapor Deposition", J. Vac. Sci. Technol. A 16(6), American Vacuum Society, pp 3190-3198, 1998.				
0	C6	AS da Silva Sobrinho et al, "Plasma-Deposited Silicon Oxide and Silicon Nitride Films on Poly(ethylene terephthalate): A Multitechnique Study of the Interphase Regions", pp. 60-208, 1998.				
	C7					
	C8					

EXAMINER



DATE CONSIDERED

2/2/04

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant